

IN THE SPECIFICATION

Please amend the paragraph at page 11, lines 6-9, as follows:

In the rotary type CVD film forming apparatus for mass production ~~described in~~ ~~Claim 1~~, preferably said housing spaces are arranged side by side at equal intervals on the same circle which uses the central axis of said external electrode as a center point.

Please amend the paragraph at page 11, lines 10-15, as follows:

In the rotary type CVD film forming apparatus for mass production ~~described in~~ ~~Claim 1 or 2~~, preferably two housing spaces are provided in one external electrode, and said film forming chambers are arranged at equal intervals on said rotation support body so that said housing spaces are arranged on the same circle which uses the rotation axis of said rotation support body as a center point.

Please amend the paragraph at page 11, line 16 to page 12, line 2, as follows:

In the rotary type CVD film forming apparatus for mass production ~~described in~~ ~~Claim 1 or 2~~, preferably two housing spaces are provided in one external electrode, and when said film forming chambers are arranged on said rotation support body, one housing space is arranged outside a circle formed by each of said film forming chambers and the other housing space is arranged inside said circle, whereby the housing spaces of said external electrodes are arranged in two rows in the circumferential direction of said circle.

Please amend the paragraph at page 12, lines 3-13, as follows:

In the rotary type CVD film forming apparatus for mass production ~~described in~~ ~~Claim 1 or 2~~, preferably three housing spaces are provided in one external electrode, and when said film forming chambers are arranged on said rotation support body, a relationship is

formed so that two housing spaces of every other film forming chamber are arranged outside the circle formed by the film forming chambers with the remaining one housing space arranged inside said circle, and two housing spaces of the adjacent film forming chambers are arranged inside said circle with the remaining one housing space arranged outside said circle, whereby the housing spaces of said external electrodes are arranged in two rows in the circumferential direction of said circle.

Please amend the paragraph at page 12, lines 14-21, as follows:

In the rotary type CVD film forming apparatus for mass production ~~described in~~ ~~Claim 1 or 2~~, preferably four housing spaces are provided in one external electrode, and when said film forming chambers are arranged on said rotation support body, two housing spaces are arranged outside a circle formed by the film forming chambers, and the other two housing spaces are arranged inside said circle, whereby the housing spaces of said external electrodes are arranged in two rows in the circumferential direction of said circle.

Please amend the paragraph at page 13, lines 1-7, as follows:

In the rotary type CVD film forming apparatus for mass production ~~described in~~ ~~Claim 4 or 6~~, preferably when said film forming chambers are arranged on said rotation support body, said housing spaces are arranged in two rows in the circumferential direction of said circle with said circle interposed between mutually adjacent housing spaces, or said housing spaces are arranged in two rows in said circumferential direction with said circle interposed between mutually shifted housing spaces.

Please amend the paragraph at page 13, lines 8-20, as follows:

Further, the method of forming a CVD film on the internal surfaces of plastic containers according to the present invention carries out a container loading process which loads said plastic containers in said film forming chambers by housing said plastic containers in said housing spaces, a pre-film-formation gas adjustment process which replaces the inside of said plastic containers with a source gas adjusted to a prescribed film forming pressure, a CVD film forming process which converts said source gas to plasma and forms a CVD film on the internal surfaces of said plastic containers, a post-film-formation gas adjustment process which opens the inside of coated plastic containers to the atmosphere, and a container removal process which removes said coated containers from said film forming chambers during the time the rotation support body ~~described in Claims 1-7~~ undergoes one rotation at a fixed speed.

Please amend the paragraph at page 13, line 21 to page 14, line 3, as follows:

In the rotary type CVD film forming apparatus for mass production ~~described in Claims 1-7~~ and in the method of forming a CVD on the internal surfaces of plastic containers ~~described in Claim 8~~, preferably a hydrocarbon gas or a Si-containing hydrocarbon gas is used as said source gas, and a DLC film is formed as said CVD film.

Please amend the paragraph at page 22, lines 10-22, as follows:

The internal electrodes 9a, 9c are arranged to be freely inserted into and removed from the inside of the external electrode 3, and are arranged in the inside of the plastic containers 7a, 7c. Namely, the internal ~~electrode~~ electrodes 9a, 9c are inserted from above the cover 4b through the space inside the cover 4b and the opening of the cover 4b and the

insulating member 4a into the housing spaces 40a, 40c inside the external electrode 3. The base ends of the internal electrodes 9a, 9c are arranged above the cover 4b. On the other hand, the tips of the internal electrodes 9a, 9c are arranged in the inside of the plastic containers 7a, 7c housed inside the housing spaces 40a, 40c of the external electrode 3. The internal electrodes 9a, 9c have tube shapes which are hollow on the inside. Gas blowout holes 49a, 49c are provided in the tips of the internal ~~electrode~~ electrodes 9a, 9c. Further, the internal electrodes 9a, 9c are preferably grounded.

Please amend the paragraph at page 25, lines 13-18, as follows:

In Fig. 3 and Fig. 4, the internal ~~electrode~~ electrodes 9a ~ 9d which correspond respectively to the housing spaces 40a, 40b, 40c, 40d are provided for the one columnar body external electrode 3. Each of the internal electrodes is grounded, and forms a pipeline which can supply a source gas to each container. In the present drawings, the internal electrodes also serve as source material supply pipes.